

METHOD FOR GENERATING DIFFERENT PHASES OF COPPER SULPHIDE NANOSTRUCTURES USING ELECTROSPRAY DEPOSITION (ESD) UNDER AMBIENT CONDITIONS

IITM Technology Available for Licensing

Problem Statement

- Currently Chemical Vapor Deposition (CVD) is the most common synthetic method, extensively used for making high quality atomic layer thin films of copper sulphide for different applications, where **high temperature processing is required for making such materials for electronic applications**
- Hence, there is a long felt need for synthesising specific **copper sulphide nanostructures under ambient conditions for practically viable applications**

Technology Category/Market

Category – Advance Material and Manufacturing

Applications –Drug delivery systems, batteries, semiconductors, photocatalysis, sensors,

Industry - Biomedical, Electrical

Market -The global **nanomaterials market size** was valued at **USD 11.43 billion in 2022** and it is expected to hit **USD 43.1 billion by 2030**, registering growth at a **CAGR of 18.05% from 2022 to 2030**.

Key Features / Value Proposition

Technical perspective

- Generates different phases of copper sulphide nanostructures -**Chalcocite (Cu_2S)** nanopyramids are formed by superionic diffusion of sulphur into copper, **digenite ($\text{Cu}_{1.8}\text{S}$)** platelets are formed by slow ionic diffusion of sulphur ions through lattice vacancies in **Cu_2S** nanopyramid
- Cu_2S** exhibits **positive photocurrent response** under electrochemical conditions
- $\text{Cu}_{1.8}\text{S}$ platelets** exhibit **sharp metallic conductance** due to accumulation of free charge carriers

User perspective

- Efficient method to synthesize specific copper sulphide nanostructures under **ambient conditions**
- Does not require solvent and harsh synthetic conditions**

Technology

- The present invention discloses a method of **generating different phases of copper sulphide nanostructures under ambient temperature using electrospray deposition (ESD)**. The said method comprising:

1. spraying sulphur in the form of droplets on a metallic copper surface for 2 to 5 min

2. generating nanopyramids of 1 to 2 mm edge length

3. subsequent spraying of sulphur over the nanopyramids for more than 5 mins

4. generating platelets on top of the nanopyramids

Image

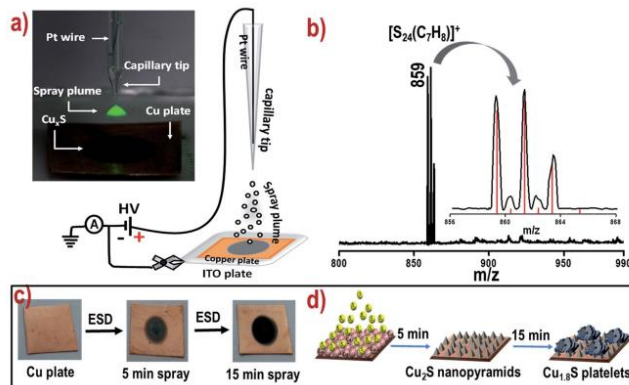


Fig. 1 (a) Schematic representation of the ESD set-up (inset shows the optical image of the 25 spray plume), (b) ESI-MS spectrum of sulphur solution (inset spectrum in black shows the experimental spectrum and red lines show the theoretical spectrum), (c) time-dependent evolution of a black circular spot during ESD, and (d) schematic representation of the growth mechanism of chalcocite (Cu_2S) nanopyramids and digenite ($\text{Cu}_{1.8}\text{S}$) platelets during ESD.

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Images

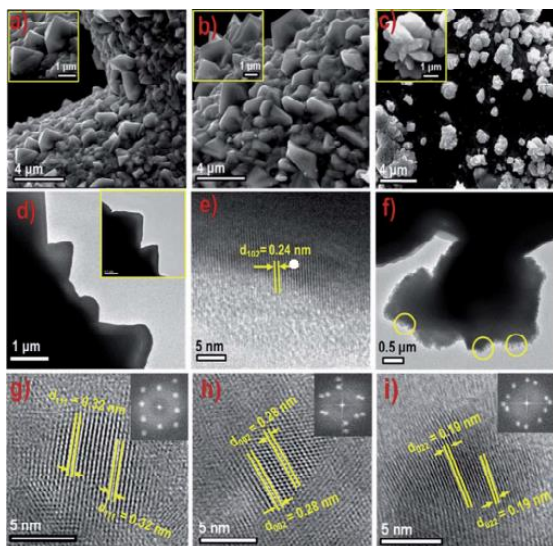


Fig. 2 (a–c) Large area SEM images at different times of deposition: (a) 2 min spray, (b) 30 min spray, and (c) 15 min spray (inset shows a higher magnification SEM image), (d) low magnification TEM image of Cu_2S nanopryramids (inset depicts the higher magnification TEM image), (e) HRTEM of Cu_2S nanopryramids, (f) TEM image of $\text{Cu}_{1.8}\text{S}$ platelets, and (g–i) HRTEM image of $\text{Cu}_{1.8}\text{S}$ platelets. Lattice parameters are marked and inset images show the corresponding FFT patterns

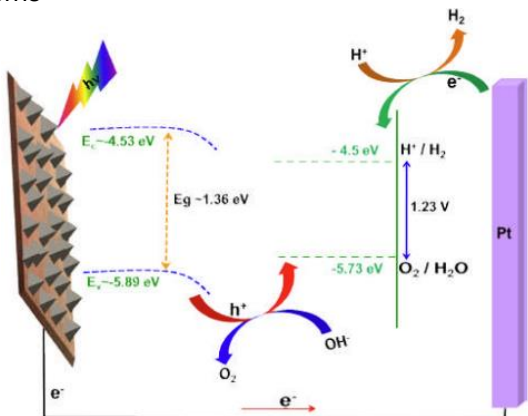


Fig. 3 Schematic representation of the photoelectrochemical process at Cu_2S nanopryramids

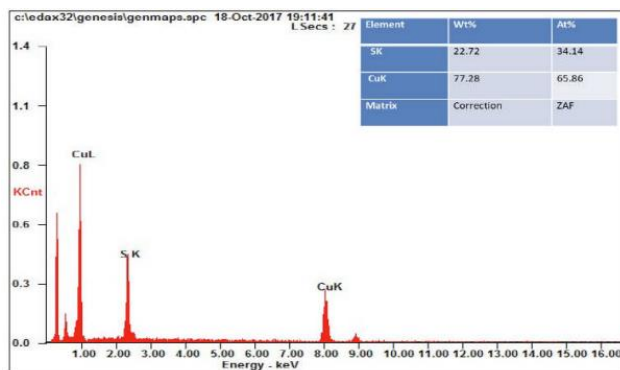


Fig. 4 EDAX spectrum of the Cu_2S nanopryramids (inset shows the elemental distribution of the Cu_2S nanopryramids)

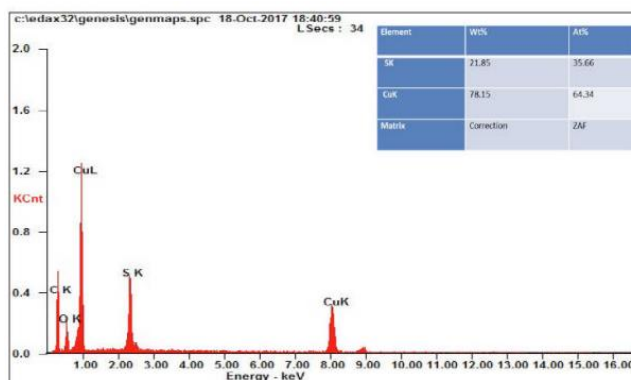


Fig. 5 EDAX spectrum of the $\text{Cu}_{1.8}\text{S}$ platelets (inset shows the elemental distribution for the $\text{Cu}_{1.8}\text{S}$ platelets).

Intellectual Property

- IITM IDF Ref. 1895
- IN 396273-Granted

TRL (Technology Readiness Level)

TRL-3, Experimental proof of concept

Research Lab

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